

Inventor: Y. Hishiro

Title: Methods of Forming Semiconductor Constructions

Assignee: Micron Technology, Inc.

INFORMATION DISCLOSURE STATEMENT

PURSUANT TO 37 C.F.R. §§1.56, 1.97 AND 1.98

In compliance with 37 C.F.R. §§1.56, 1.97 and 1.98, your attention is directed to the United States patents and other references listed on the attached Form PTO-1449.

The listed references were cited by, or submitted to, the Office in the parent, co-pending application of the above-identified application. The above-identified application is a continuation of co-pending application Serial No. 10/092,874 filed March 5, 2002. Such prior disclosure is sufficient for the above-identified application as far as copies of the references are concerned. 37 C.F.R. §1.98(d) and MPEP §609(2). No admission is made regarding whether all the submitted references are prior art.

Citation of these references is respectfully requested.

Respectfully submitted,

Dated: 2/19/2004

Attorney: 

David G. Latwesen, Ph.D. Reg. #38,533
WELLS ST. JOHN P.S.

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EL979953725

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-2507		PRIORITY SERIAL NO. 10/092,874	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Micron Technology, Inc.			
				PRIORITY FILING DATE March 5, 2002		PRIORITY GROUP 2814	
U.S. PATENT DOCUMENTS							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	US 2002/0045130 A1	4/18/02	Nitta et al.			
	AB	US 2003/0008246 A1	1/9/03	Cheng et al.			
	AC	6,403,280	6/11/02	Yamahara et al.			
	AD	6,136,511	10/24/00	Reinberg et al.			
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
							Yes No
	AK						
	AL						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
	AM		"Chemically Amplified Photoresists" , IBM: http://www.almaden.ibm.com/st/projects/sub100nm/objectives/ca/				
	AN		"Imaging of photogenerated acid in a chemically amplified photoresist" ; S. J. Bukofsky et al.; 1998 American Institute of Physics, Vol. 73, No. 3, 20 July 1998, pp. 408-410				
	AO						
	AP						
EXAMINER				DATE CONSIDERED			
<small>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</small>							